

### **Amendments to the Claims**

This listing of claims will replace all prior versions, and listings of claims in the application.

#### **Listing of Claims:**

1-14. (cancelled).

15. (currently amended) A chemical vapor deposition apparatus comprising:

a load-lock chamber;

a processing chamber mounted on said load-lock chamber;

an air purge line adapted to supply and exhaust gas connected with said load-lock chamber, wherein said air purge line supplies the load-lock chamber with air including H<sub>2</sub>O gas; and,

a vacuum pump connected to the air purge line and adapted to exhaust the residual gases from the load-lock chamber.

16. (previously presented) The apparatus as recited in claim 15, further comprising:

a vent line connected to the load-lock chamber and adapted to provide an inert gas to the load-lock chamber.

17. (previously presented) The apparatus as recited in claim 16, wherein said vent line is connected to said vacuum pump.

18. (previously presented) The apparatus as recited in claim 17, further comprising an O<sub>2</sub> gas line connected to said air purge line.

19. (previously presented) The apparatus as recited in claim 18, further comprising a filter connected to said air purge line.

20. (cancelled)

21. (original) The apparatus as recited in claim 18, wherein the O<sub>2</sub> gas line is connected to the vacuum pump.

22. (original) The apparatus as recited in claim 18, further comprising mass flow controllers connected to the air purge line, the vent line and the O<sub>2</sub> gas line so as to regulate flows and amounts of the air including H<sub>2</sub>O, the inert gas and O<sub>2</sub> gas, respectively.